

THE INFLUENCE OF ADDITIVES ON WO₃ THIN FILM DEPOSITION

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Abstract: *The aim of the papers is to describe the influence of the additives on the process of film formation. The thermal reactions were investigated using DSC analysis and the crystalline structure of the samples was revealed via XRD studies. The conductivity behavior depends on various factors investigated in the I-V graphics. Finally, the concentration of defect density was determined by impedance analysis.*

Key words: *tungsten trioxide, additives, nanostructured.*